

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants : Dureseti CHIDAMBARRAO, et al. Group Art Unit: 2814  
Appln. No. : 10/605,108 Examiner: PHAM, Long  
Filed : September 9, 2003 Confirmation No. 2107  
For : METHOD FOR REDUCED N+ DIFFUSION IN STRAINED SI  
ON SI/GE SUBSTRATE

**RESPONSE UNDER 37 C.F.R. 1.116**

Commissioner for Patents  
U.S. Patent and Trademark Office  
Customer Window, Mail Stop AF  
Randolph Building  
401 Dulany Street  
Alexandria, VA 22314  
Sir:

Responsive to the Final Official Action of June 8, 2006, reconsideration and withdrawal of the rejections made therein are respectfully requested, in view of the following remarks.

A listing of the claims begin on page 2; and

Remarks begin on page 7.

Inasmuch as the Official Action sets a three-month shortened statutory period which expires September 8, 2006, this Amendment is being timely filed and no extension of time is believed necessary. However, if an extension is deemed by the Patent and Trademark Office to be necessary, the same is hereby requested and the Patent and Trademark Office is hereby authorized to charge any necessary fees in connection therewith or any fees necessary to preserve the pendency of this application to deposit account No. 09-0458.